

**Search Notes**

Application/Control No.

10/696,079

Examiner

Anh D. Mai

Applicant(s)/Patent under  
Reexamination

LIM ET AL.

Art Unit

2814

**SEARCHED**

Class	Subclass	Date	Examiner
438	199; 275 283; 770	3/17/2005	A.M

**INTERFERENCE SEARCHED**

Class	Subclass	Date	Examiner

**SEARCH NOTES  
(INCLUDING SEARCH STRATEGY)**

	DATE	EXMR
EAST (all) * Inventors * CCLS * (dual gate oxide) and (resist or photoresist) and (ash or ashing) * piranha and clean and ash	3/17/2005	A.M
IEEE explore: dual gate oxide	3/16/2005	A.M